Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L9	9	18 and (I near shaped near spacer)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/06 12:49
L10	9	18 and (I near shaped near spacer) and spacer	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/06 12:49
L11	7	I8 and (I near shaped near spacer) and spacer.clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/06:12:50
L12	5	l8 and (I near shaped near spacer).clm. and spacer.clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/06 12:50
L13	2	l8 and (I near shaped near spacer).clm. and sidewall.clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/06 12:50
L14	19	(I near shaped near spacer).clm. and sidewall.clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/06 12:50
L15	2	(I near shaped near spacer).clm. and sidewall.clm. and liner.clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/06 12:50
L16	19	(I near shaped near spacer).clm. and sidewall.clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/06 12:51
L17	11	(I near shaped near spacer).clm. and sidewall.clm. and (silicon adj nitride).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/06 12:53

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L18	5	(I near shaped near spacer).clm. and sidewall.clm. and (silicon adj nitride).clm. and polysilicon.clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON ·	2005/01/06 12:53
L19	10	(I near shaped near2 spacer).clm. and sidewall.clm. and (silicon adj nitride).clm. and polysilicon.clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/06:12:54
L20	5	(I near shaped near2 spacer).clm. and sidewall.clm. and (silicon adj nitride).clm. and polysilicon.clm. and liner.clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/06 12:55
L21	1	(I near shaped near2 spacer).clm. same sidewall.clm. same (silicon adj nitride).clm. same polysilicon. clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/06 12:55
L22	5	(I near shaped near2 spacer).clm. and sidewall.clm. and (silicon adj nitride).clm. and polysilicon.clm. and liner.clm. and spacer.ab.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/06 12:55
L23	10	(I near shaped near2 spacer).clm. and sidewall.clm. and (silicon adj nitride).clm. and polysilicon.clm. and spacer.ab.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/06 12:55
L24	. 10	(I near shaped near2 spacer).clm. and sidewall.clm. and (silicon adj nitride).clm. and polysilicon.clm. and spacer.ab.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/06 12:56
L25	19001	(I near shaped near2 spacer).clm. and sidewall.clm. and (silicon adj nitride).clm. and polysilicon.clm. and spacer.ab. (sti or (shallow near trench))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/06 12:57
L26	3	(I near shaped near2 spacer).clm. and sidewall.clm. and (silicon adj nitride).clm. and polysilicon.clm. and spacer.ab. and (sti or (shallow near trench))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/06 13:00
L27	0	(I near shaped near2 spacer).clm. and sidewall.clm. and (silicon adj nitride).clm. and polysilicon.clm. and spacer.ab. and (sti or (shallow near trench)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/06 13:01

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L28	10	(I near shaped near2 spacer).clm. and sidewall.clm. and (silicon adj nitride).clm. and polysilicon.clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/06 13:03
L29	4	((polysilicon adj trace) near5 gate).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/06 13:03
L30	3	((polysilicon adj trace) near5 gate).clm. and (I near shaped near2 spacer).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/06 14:00
L31	3	I30 and (liner near5 (overy or overlying) near5 trace)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/06 14:09
L32	3	l30 and (polysilicon near5 trace)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/06 14:09